L	Hits	Search Text	DB	Time stamp
Number	HILS	Scaron leve	100	
6	0	<pre>(phase with change) same (HSG or (hemispheric adj grain) or (hemispheric adj grained) or (hemispherical adj grained))</pre>	USPAT; US-PGPUB	2004/09/22 09:29
7	21	(phase with change) and (HSG or (hemispheric adj grain) or (hemispheric adj grained) or (hemispherical adj grained))	USPAT; US-PGPUB	2004/09/22 09:58
8	0	(phase near3 changeable) and (HSG or (hemispheric adj grain) or (hemispheric adj grained) or (hemispherical adj grained))	USPAT; US-PGPUB	2004/09/22 09:57
9	14	(programmable near3 material) and (HSG or (hemispheric adj grain) or (hemispheric adj grained) or	USPAT; US-PGPUB	2004/09/22 09:57
10	0	<pre>(hemispherical adj grained)) (recordable near3 material) and (HSG or (hemispheric adj grain) or (hemispheric adj grained) or (hemispherical adj grained))</pre>	USPAT; US-PGPUB	2004/09/22 09:57
11	35	(memory near3 material) and (HSG or (hemispheric adj grain) or (hemispheric adj grained) or (hemispherical adj grained))	USPAT; US-PGPUB	2004/09/22
12	0	(recording near3 material) and (HSG or (hemispheric adj grain) or (hemispheric adj grained) or (hemispherical adj grained))	USPAT; US-PGPUB	2004/09/22 09:56
13	0	(recording near3 material) and (HSG or (hemispheric adj grain) or (hemispheric adj grained) or (hemispherical adj grained))	EPO; JPO; DERWENT; IBM_TDB	2004/09/22 09:56
14		(memory near3 material) and (HSG or (hemispheric adj grain) or (hemispheric adj grained) or (hemispherical adj grained))	EPO; JPO; DERWENT; IBM_TDB	2004/09/22
15	0	(recordable near3 material) and (HSG or (hemispheric adj grain) or (hemispheric adj grained) or (hemispherical adj grained))	EPO; JPO; DERWENT; IBM_TDB	2004/09/22
16	0	(programmable near3 material) and (HSG or (hemispheric adj grain) or (hemispheric adj grained) or (hemispherical adj grained))	EPO; JPO; DERWENT; IBM_TDB	2004/09/22 09:57
17	0	(phase near3 changeable) and (HSG or (hemispheric adj grain) or (hemispheric adj grained) or (hemispherical adj grained))	EPO; JPO; DERWENT; IBM_TDB	2004/09/22 09:58
18	0	(phase with change) and (HSG or (hemispheric adj grain) or (hemispheric adj grained) or (hemispherical adj grained))	EPO; JPO; DERWENT; IBM_TDB	2004/09/22 09:58
19	1334	438/93-95,398,602.ccls. and @ad<20011231	USPAT; US-PGPUB	2004/09/22 10:02
21	382	(438/93-95,398,602.ccls. and @ad<20011231) and (HSG or (hemispheric adj grain) or (hemispheric adj grained) or (hemispherical adj grained))	USPAT; US-PGPUB	2004/09/22
22	667	257/3,4,200,246.ccls. and @ad<20011231	USPAT; US-PGPUB	2004/09/22 10:02
24	0	(257/3,4,200,246.ccls. and @ad<20011231) and (HSG or (hemispheric adj grain) or (hemispheric adj grained) or (hemispherical adj grained))	USPAT; US-PGPUB	2004/09/22
25	667		USPAT; US-PGPUB	2004/09/22 10:04

26	2223	(phase adj change) and adhesion	USPAT;	2004/09/22	_
ŀ			US-PGPUB	10:05	
27	398	(phase adj change adj material) and	USPAT;	2004/09/22	
		adhesion	US-PGPUB	10:05	
28	228	((phase adj change adj material) and	USPAT;	2004/09/22	
		adhesion) and @ad<20011231	US-PGPUB	10:05	
29	73	(phase adj change adj material) same	USPAT;	2004/09/22	
		adhesion	US-PGPUB	10:05	ı
30	52	((phase adj change adj material) same	USPAT;	2004/09/22	
		adhesion) and @ad<20011231	US-PGPUB	10:05	- 1

DOCUMENT-IDENTIFIER: US 20030001211 A1

TITLE: MODIFIED CONTACT FOR PROGRAMMABLE

DEVICES

----- KWIC -----

Detail Description Paragraph - DETX (29):

[0056] As further illustrated in FIG. 16, following the introduction of

programmable material 404, barrier material 408 is formed on programmable

material 404 and conductor 410 is formed on barrier material 408, in accordance

with an embodiment. Barrier material 408 serves, in an aspect, to prevent any

chemical reaction between programmable material 404 and conductor 410. In an

embodiment, programmable material 404, spacer 402, barrier material 408 and

conductor 410 are formed using conventional patterning techniques. In an

embodiment, barrier material 408 includes at least one of titanium and titanium

nitride. Titanium and/or Titanium nitride coatings can be deposited uniformity

on a substrate, showing good <u>adhesion</u> in that they resist flaking, blistering,

chipping and peeling. In an embodiment, programmable material 404 includes a

phase change material of a chalcogenide alloy and contact
170 includes

CoSi.sub.2. In an embodiment, chalcogenide alloys suitable as programmable

material 404 include at least one element from column VI of the Periodic Table

Of The Elements. In an embodiment,

Ge.sub.2Sb.sub.2Te.sub.5 is utilized as

programmable material 404. Other chalcogenide alloys utilized as programmable

material 404 include GaSb, InSb, InSe, Sb.sub.2Te.sub.3, GeTe.

Ge.sub.2Sb.sub.2Te.sub.5, InSbTe, GaSeTe, SnSb.sub.2Te.sub.4, InSbGe, AgInSbTe,

(GeSn)SbTe, GeSb(SeTe), and Te.sub.81Ge.sub.15Sb.sub.2S-.sub.2.